

METHOD AND DEVICE FOR CORRECTING PROXIMITY EFFECTS**ABSTRACT OF THE DISCLOSURE**

The present invention relates to a method for determining the precompensated pattern of exposure doses of an electron beam required per pattern position to obtain a desired pattern in a coating on a substrate, comprising the steps of: determining a smearing function of the electron beam; determining a precompensated pattern with the smearing function and the desired pattern, wherein the determination is performed such that exposure doses contain almost exclusively positive values and the exposure doses are smooth relative to each other.

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